

REMARKS

Claim 16 has been amended to include the subject matter of claim 17.

Claim 17 was rejected based on the assertion that Avanzino shows greater than 50% porosity. This is apparently based on the schematic figure. Clearly, the schematic figure was never intended to graphically depict the actual porosity. Instead, a graphic symbol was used. The porosity will most certainly not be of the size depicted in the figure and the figure most certainly cannot be taken as actually showing the physical pores.

The way the porosity was achieved, in one embodiment in the present invention, is to use electron beams with sonication. No special technique was described of the sort in the cited reference. Thus, there is no way that the cited reference would have gotten the high porosity achieved through special techniques in connection with the present application.

Thus, the rejection, based on the graphic symbols used in the reference, is insufficient to meet claim 16 as amended. Therefore, reconsideration is requested.

New claim 24 calls for a structure like original claim 16, limited to carbon doped oxide. While it is pointed out that the Kumar reference teaches carbon doped oxide, he does not teach carbon doped oxide with the characteristics set forth in the claim. Namely, there is no teaching of how to make porous carbon doped oxide. Therefore, there is no teaching of how to make the structure claimed.

In other words, merely saying that carbon doped oxide could be utilized does not teach that carbon doped oxide could be utilized in a way to make smooth conductive metal lines against the oxide, and then forming the porosity.

The carbon doped oxide dielectric may undergo carbon depletion during treatment with an electron beam. See the bottom of page 9 and the top of page 10. The carbon chains may produce larger pores and a higher degree of porosity.


There is no suggestion of any way to make carbon doped oxide porous and no suggestion of using electron beams to do so.

Therefore, there is no teaching of how to make smooth metal lines adjacent to the carbon doped oxide.

In view of these remarks, the application should now be in condition for allowance.

Respectfully submitted,

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Timothy N. Trop, Reg. No. 28,994
TROP, PRUNER & HU, P.C.
8554 Katy Freeway, Ste. 100
Houston, TX 77024
713/468-8880 [Phone]
713/468-8883 [Fax]

Attorneys for Intel Corporation